

A Coaxial Dielectric Barrier Discharge for Fluorocarbon Conversion

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Fluorocarbons conversion has been studied widely because fluorocarbons are powerful of greenhouse gases. Moreover, fluorocarbons such as C_2F_6 used in the plasma etching and chemical vapor deposition process of semiconductor industry. Therefore, fluorocarbons in the gas outlet of the process must be removed before gas waste into the air. In this study, a coaxial dielectric barrier discharge plasma reactor employed for fluorocarbons conversion. Several of factors of process will be considered such as applied voltage, resident time. These parameters will consider aspects to reactant conversion.